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6 Nonequilibrium Atmospheric Pressure Discharges and Plasmas

Sommario/riassunto

Written by a university lecturer with more than forty years experience in plasma technology, this book adopts a didactic approach in its coverage of the theory, engineering and applications of technological plasmas. The theory is developed in a unified way to enable brevity and clarity, providing readers with the necessary background to assess the factors that affect the behavior of plasmas under different operating conditions. The major part of the book is devoted to the applications of plasma technology and their accompanying engineering aspects, classified by the various pressure and de